Accepted Manuscript

Transfer-free chemical vapor deposition of graphene on silicon substrate at atmospheric pressure: A sacrificial catalyst

thin sold films

Samira Naghdi, Kyong Yop Rhee, Soo Jin Park

PII: S0040-6090(18)30311-0

DOI: doi:10.1016/j.tsf.2018.05.004

Reference: TSF 36647

To appear in: Thin Solid Films

Received date: 23 December 2017
Revised date: 20 April 2018
Accepted date: 2 May 2018

Please cite this article as: Samira Naghdi, Kyong Yop Rhee, Soo Jin Park, Transfer-free chemical vapor deposition of graphene on silicon substrate at atmospheric pressure: A sacrificial catalyst. The address for the corresponding author was captured as affiliation for all authors. Please check if appropriate. Tsf(2017), doi:10.1016/j.tsf.2018.05.004

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

ACCEPTED MANUSCRIPT

Transfer-free chemical vapor deposition of graphene on silicon substrate at atmospheric pressure: A sacrificial catalyst

Samira Naghdi¹, Kyong Yop Rhee^{1,*}, Soo Jin Park ^{2,**}

¹Department of Mechanical Engineering, College of Engineering, Kyung Hee University, 446-701, Yongin, Korea

²Department of Chemistry, College of Natural Science, Inha University, 402-751, Incheon, Korea

*Corresponding author. Tel: +82 31 201 2565, Fax: +82 31 202 6693, rheeky@khu.ac.kr (K. Rhee)

**Co-corresponding author. Tel: +82 32 876 7234, Fax: +82 32 860 8438, sjpark@inha.ac.kr (S. J. Park)

Download English Version:

https://daneshyari.com/en/article/8032575

Download Persian Version:

https://daneshyari.com/article/8032575

<u>Daneshyari.com</u>